

Atty.  
Dkt. No.

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Client Ref.

273243

PC0033A Reg

**INFORMATION DISCLOSURE STATEMENT  
BY APPLICANT**

Applicant: JOHNSON et al.

Appln. No.: Not Yet Assigned

Filing Date: February 15, 2002

Date: February 15, 2002

Page

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of

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Examiner: Not Assigned

Group Art Unit: Not Asgnd

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Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
<i>me</i>	AR	4,824,690	04/1989	HEINECKE et al.	313	231.31	
	BR	4,891,118	01/1990	OOIWA	304	231.31	
	CR	4,935,661	06/1990	HEINECKE et al.	313	231.31	
<i>me</i>	DR	4,993,358	02/1991	MAHAWILI	118	715	
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	JR						
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		Document Number	Date MM/YYYY	Country	Inventor Name		English Abstract	Translation Readily Available
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**OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)**

	YR							
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PC0033A 2

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Applicant: JOHNSON et al.

Appln. No.: 10/076,099

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Date: July 19, 2002

Page 1 of 4

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Group Art Unit: 1762

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	CR 4,935,661	06/1990	HEINECKE et al.	313	23.31	
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	FR 4,500,563	02/1985	ELLENBERGER et al.	427	710	
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<i>for</i>	RR	Bird, Molecular Gas Dynamics and the Direct Simulation of Gas Flows, Claredon Press, 1994, pp. 2-3.-			
	SR	Gentry et al., "Ten-microsecond pulsed molecular beam source and a fast ionization detector," Rev. Sci. Instru, 49(5), May 1978, pp. 595-600.			
	TR	Samukawa et al., "Pulse-time modulated electron cyclotron resonance plasma etching for highly selective, highly anisotropic, and less-charging polycrystalline silicon patterning," J. Vac. Sci. Technol. B 12(6), Nov/Dec 1994, pp. 3300-3305.			
	UR	Sugai et al., "Diagnostics and control of high-density etching plasmas," Mat. Res. Soc. Symp., Proc. Vol 406, 1996, pp. 15-25.			
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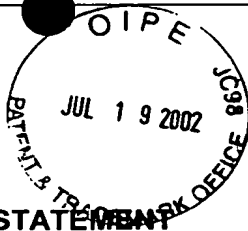
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*Barney W. Smith*

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Page

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of

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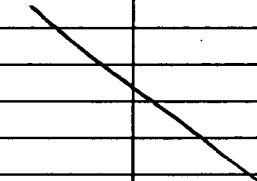
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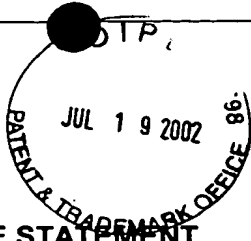
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TR	Kendall, "Pulsed gas injection for on-line calibration of residual gas analyzers," J. Vac. Sci. Technol. A 5(1), Jan/Feb 1987, pp. 143-148.			
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VR	Saenger, "Pulsed molecular beams: a lower limit on pulse duration for fully developed supersonic expansions," J. Chem. Phys. 75(5), 1 Sept. 1981, pp. 2467-2469.			
WR	Bassi et al., "Pulsed molecular beam source," Rev. Sci. Instrum. 52(1), Jan 1981, pp. 8-11.			

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Page 3 of 4

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Group Art Unit: 1762

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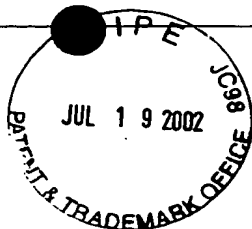
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WR	Ono et al., "Selectivity and profile control of poly-Si etching by time modulation bias method," 1998 Dry Process Symposium, V-1, pp. 141-146.				

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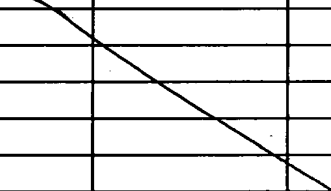
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UR	Samukawa, "Highly selective and highly anisotropic SiO2 etching in pulse-time modulated electron cyclotron resonance plasma," Journal of Appl. Phys. Vol. 33 (1994), Pt. 1, No. 4B, pp. 2133-2138.			
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WR				

Examiner

*Robert McDonald*

Date Considered:

*9/4/03*

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